## High-performance polymer field-effect transistors fabricated with low-bandgap DPPbased semiconducting materials

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- S1. Thermogravimetric analysis (TGA) of PDMOTT-n.
- S2. Electrochemical properties of **PDMOTT-***n*.
- S3. AFM topography images of **PDMOTT-***n* pristine thin films.
- S4. 1D-GIXRD patterns of the PDMOTT-n thin films
- S5. <sup>1</sup>H and <sup>13</sup>C NMR spectra of intermediates **2** and **3**.

S1. Thermogravimetric analysis (TGA) of PDMOTT-n.



Fig. S1 TGA traces of copolymers PDMOTT-n.

**S2.** Electrochemical properties of **PDMOTT**-*n*.



Fig. S2 CV traces of copolymers PDMOTT-n.

- (a)
   RMS = 0.46 nm
   (b)
   RMS = 0.47 nm
   20 nm

   (a)
   (b)
   RMS = 0.47 nm
   0 nm

   (c)
   RMS = 3.14 nm
   (d)
   RMS = 3.08 nm
   50 nm

   (c)
   RMS = 3.14 nm
   (d)
   RMS = 3.08 nm
   50 nm
- **S3**. AFM topography images of **PDMOTT**-*n* pristine thin films.

Fig. S3 AFM topography images of PDMOTT-*n* pristine thin films on OTS-modified SiO<sub>2</sub>/Si substrates. (a) PDMOTT-*118*, (b) PDMOTT-*122*, (c) PDMOTT-*320* and (d) PDMOTT-*420*. All images are 5  $\mu$ m × 5 $\mu$ m in size.

S4. 1D-GIXRD patterns of the PDMOTT-*n* thin films



**Fig. S4** GIXRD patterns of the **PDMOTT***-n* thin films after annealing at 180 °C. (a) Out-of-plane X-ray diffraction pattern. (b) In-plane X-ray diffraction pattern.

**S5.** <sup>1</sup>H and <sup>13</sup>C NMR spectra of intermediates **2** and **3**.







